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(54) Title: SHIELDING FOR IMMERSED PLASMA SOURCE

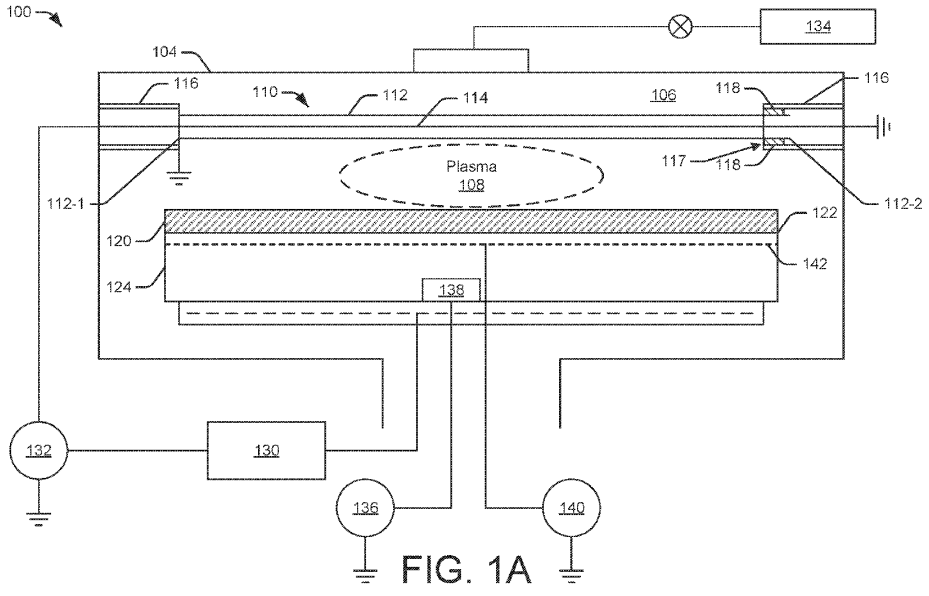


FIG. 1A

(57) Abstract: Embodiments of the disclosure include apparatus which includes a metal shield having a first end, a second end, and an inner bore disposed between the first end and the second end. The inner bore is defined by a wall of the metal shield extending from the first end to the second end. The first end includes an electrically grounded portion. A radio frequency (RF) antenna is disposed at least partially in the inner bore. One or more apertures are formed between the RF antenna and a plasma processing region of a plasma processing chamber. A dielectric material covers the one or more apertures. The RF antenna is configured to deliver RF power to the processing region of the plasma processing chamber through the dielectric material.

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WO 2025/193369 A1

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